1. (Original) A resist polymer at least having a repeating unit having a structure which is decomposed by an acid to become soluble in an alkali developer and a repeating unit having a polar group to enhance adhesion to a substrate, characterized in that a peak area of a high molecular weight component (high polymer) with molecular weight of 100,000 or more is 0.1% or less based on an entire peak area in a molecular weight distribution determined by gel permeation chromatography (GPC).

2. (Original) The resist polymer according to claim 1, wherein said polymer is produced by radical copolymerization with retaining a solution containing polymerizable monomers and a solution containing a polymerization initiator in respectively independent storage tanks and supplying into a polymerization system continuously or intermittently.

3. (Original) A method for producing a resist polymer at least having a repeating unit having a structure which is decomposed by an acid to become soluble in an alkali developer and a repeat unit having a polar group to enhance adhesion to a substrate, characterized in that radical copolymerization is performed by retaining a solution containing polymerizable monomers and a solution containing a polymerization initiator

in independent storage tanks respectively and supplying them into a polymerization system continuously or intermittently.

4. (Original) The method for producing the resist polymer according to claim 3, wherein the solution containing the polymerizable monomers is previously heated before being supplied to polymerization system.

5. (Currently Amended) The method for producing the resist polymer according to ~~claims 3 or 4~~ claim 4, wherein supplying the solution containing the polymerization initiator to polymerization system is started prior to supplying the solution containing the polymerizable monomers.

6. (Currently Amended) The method for producing the resist polymer according to ~~any of claims 3-5~~ claim 5, wherein the solution containing the polymerizable monomers and the solution containing the polymerization initiator are mixed in a polymerization tank by continuously or intermittently supplying from the respectively independent storage tanks into a polymerization solvent heated to polymerization temperature.

7. (Currently Amended) The method for producing resist polymer according to ~~any of claims 3-6~~ claim 6, wherein the solution containing the polymerizable monomers and the solution containing the polymerization initiator are

previously mixed just before the polymerization and then continuously or intermittently supplied into the polymerization solvent heated to the polymerization temperature.

8. (Currently Amended) The method for producing the resist polymer according to ~~any of claims 3-7~~ claim 7, wherein supplying rate of either or both of the solution containing the polymerizable monomers and the solution containing the polymerization initiator to polymerization system, is changed by 2 or more steps.

9. (Currently Amended) The method for producing the resist polymer according to ~~any of claims 3-8~~ claim 8, wherein the polymerization is conducted at or above a temperature of the boiling point of polymerization solvent.